Mooney, Michael Sat 1/10/04 9:00 AM Start: Sat 1/10/04 9:30 AM End: (none) Recurrence: ((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS 199 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and SiO\$6 USPAT; US-PGPUB 2004/01/07 11:14 ((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 536 BRS orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon) **USPAT: US-**2004/01/07 11:15 **PGPUB** (((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS 172 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6)) USPAT; US-PGPUB 2004/01/07 11:40 ((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and (optic\$6 with (ax\$6 or port)) USPAT; US-PGPUB 2004/01/07 11:18 (((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 **BRS** 35 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and (optic\$6 with (ax\$6 or port))) and cavit\$6 USPAT; US-PGPUB 2004/01/07 11:36 USPAT; US-PGPUB 2004/01/07 11:35 sacrificial with etch-stop 0 BRS 66 ((((((coat\$6 with laver\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS 22 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and (optic\$6 with (ax\$6 or port))) and cavit\$6) and (sacrificial with layer\$6) USPAT: US-PGPUB 2004/01/07 11:41 ((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 USPAT; US-PGPUB 2004/01/07 11:53 with (film or coat\$6))) and ((mirror or reflect\$8) with cavit\$6) (coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 orfabricat USPAT; US-PGPUB 2004/01/08 15:11 \$6 or manufactur\$6)) and (etch\$8 with layer\$6) BRS 25 ((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and ((mirror or reflect\$8) with cavit\$6)) and (sacrificial with layer\$6) USPAT: US-**PGPUB** 2004/01/07 11:54 ((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and ((mirror or reflect\$8) with (cavit\$6 or filter or laser)) USPAT; US-PGPUB 2004/01/08 14:42 (((((coat\$6 with layer\$6) and (MEMS or MOEMS) and ((process or method) with (mak\$6 BRS 34 orfabricat\$6 or manufactur\$6)) and (etch\$8 with layer\$6)) and optic\$6 and (SiO\$6 or silicon)) and (dielectric\$6 with (film or coat\$6))) and ((mirror or reflect\$8) with (cavit\$6 or filter or laser))) and (sacrificial with layer\$6)

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5986796.pn. USPAT; US-PGPUB 2004/01/07 18:14

"20020168136" and (support with port)

USPAT; US-PGPUB 2004/01/07 17:59

0

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USPAT; US-PGPUB 2004/01/07 18:18

USPAT; US-PGPUB 2004/01/07 14:22

"20020168136"

BRS

BRS

BRS

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BRS	1	5986796.pn. and (mirror same etch\$6)	USPAT; US-PGPUB	2004/01/07 18:33	6.
BRS	1	"20020168136" and (etch-stop with optic\$6	USPAT; US-F	PGPUB 2004/01/07 21:23	
BRS	1	"20020168136" and (etch\$6 with coat\$6)	USPAT; US-PGPUB	2004/01/07 21:23	
BRS	0	5986796.pn. and (etch\$6 with coat\$6)	USPAT; US-PGPUB	2004/01/07 21:22	
BRS	0	5986796.pn. and (etch\$6 with coat\$6) and (etch	etch\$6 with \$6stop)	USPAT; US-PGPUB	
BRS	1 0	"20020168136" and (etch\$6 with coat\$6)	USPAT; US-PGPUB	2004/01/07 21:23	
BRS	1	"20020168136" and (etch-stop with optic\$6	USPAT; US-F	PGPUB 2004/01/07 21:47	
BRS	1	("20020168136" and (etch\$6 with coat\$6))	`		
BRS	1	6" and (etch\$6 with \$6stop)) USPAT; US-I "20020168136" and (device near1 layer)	USPAT; US-PGPUB		
BRS	0	"20020168136" and (etch\$6 with \$6stop)	USPAT; US-PGPUB	2004/01/07 21:28	
BRS	0	"20020168136" and (coat\$6 with optic\$6)	USPAT; US-PGPUB	2004/01/07 21:47	
with (coat\$6 BRS orfabr with (film or of (5)) same 31 ricat\$6 o film or of (5)) same 26 ricat\$6 o film or of (5)) same 14 ricat\$6 o film or of (5)) same 2004/05	((((coat\$6 with layer\$6) and (MEMS or MO r manufactur\$6)) and (etch\$8 with layer\$6)) at coat\$6))) and ((mirror or reflect\$8) with (cavithick\$6)	and optic\$6 and (SiO\$6 t\$6 or filter or laser)) a 01/08 14:48 DEMS) and ((process of and optic\$6 and (SiO\$6 t\$6 or filter or laser)) a 2004/01/08 14:49 DEMS) and ((process of and optic\$6 and (SiO\$6 t\$6 or filter or laser)) a USPAT; US-FOEMS) and ((process of and optic\$6 and (SiO\$6 t\$6 or filter or laser)) a 0 with (reflect\$6 or minutes) and ((process of and optic\$6 and (SiO\$6 t\$6 or filter or laser)) a 0 with (reflect\$6 or minutes) and ((process or minutes) and ((process or minutes)) and ((process or m	of or silicon)) and (dielectrics and ((dielectrics with (film 0) or method) with (mak\$6 or silicon)) and (dielectrics and ((dielectrics with (film 0) or method) with (mak\$6 or silicon)) and (dielectrics and ((dielectrics with (film PGPUB 2004/01/08 14:52 or method) with (mak\$6 or silicon)) and (dielectrics and ((dielectrics with (film prors with with (mak\$6 or fabrical with with with with with with with with	or \$6 or \$6 or B
15:21 BRS	22	0 (MEMS or Moems) and (dop\$6 with curvatu	,	PGPUB 2004/01/08 15:22	
MOE	•	0 ((MEMS or Moems) and (dop\$6 with curvated) ((process or method) with (mak\$6 orfabricated) (urv\$7)) USPAT; US-PGPUB 2004/01/08 15	\$6 or manufactur\$6)) a	• •	d